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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10091461	03/07/2002	438		2812	

****APPLICANTS:** Ito Masataka;

****CONTINUING DATA VERIFIED:**

**** FOREIGN APPLICATIONS VERIFIED:**
JAPAN 058745/2001 03/12/2001

PG-PUB ☐ DO NOT PUBLISH ☐ RESCIND ☐

Foreign priority claimed ☐ yes ☐ no
 35 USC 119 conditions met ☐ yes ☐ no
 Verified and Acknowledged Examiner's initials

ATTORNEY DOCKET NO
00862.022541

TITLE : SOI substrate, annealing method therefor, semiconductor device having the SOI substrate, and method of manufacturing the same

U.S. DEPT. OF COM. / PAT. & TM. PTO-476L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Sheets Drwg.	Figs. Drwg. Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		Application Examiner	
		PREPARED FOR ISSUE	
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